

## **LISTING OF THE CLAIMS**

This listing of claims will replace all prior versions, and listings, of claims in the application:

### **Claims 1-3 (Canceled)**

### **Claim 4 (Currently Amended)**

~~A The substrate processing apparatus of claim 9, wherein a processing liquid is supplied to one major surface of a substrate and one major surface is subjected to predetermined substrate processing, comprising:~~

~~an atmosphere blocking member which is faced with other major surface of said substrate and that is away from said substrate; and~~

~~a gas supplying unit which supplies an atmosphere gas to a space which is created between said atmosphere blocking member and said substrate;~~

~~wherein a substrate-facing surface of said atmosphere blocking member which is faced with the other major surface of said substrate becomes closer to said substrate with a distance toward a periphery edge of said atmosphere blocking member;~~

~~a central area of said substrate-facing surface which is faced with an approximately central portion of said substrate is a flat surface, and a periphery edge area of said substrate-facing surface which is faced with a periphery edge of said substrate is an angled surface which becomes closer to said substrate with a distance toward a periphery edge of said substrate-facing surface; and~~

~~said atmosphere blocking member has a diameter which is smaller than a diameter of said substrate by a width of a notch at a periphery edge of said substrate.~~

~~further comprising at least three or more support members which are disposed at the periphery edge of said atmosphere blocking member, abut on an edge surface of said substrate and accordingly support said substrate.~~

### **Claims 5-8 (Canceled)**

#### **Claim 9 (Currently Amended)**

A substrate processing apparatus wherein a processing liquid is supplied to one major surface of a substrate and one major surface is subjected to predetermined substrate processing, comprising:

an atmosphere blocking member which is faced with other major surface of said substrate and that is away from said substrate; and

a gas supplying unit which supplies an atmosphere gas to a space which is created between said atmosphere blocking member and said substrate,

wherein a substrate-facing surface of said atmosphere blocking member which is faced with the other major surface of said substrate becomes closer to the other major surface of said substrate with a distance toward a periphery edge of said atmosphere blocking member,

said atmosphere blocking member has a radius ~~diameter~~ which is smaller than a radius ~~diameter~~ of said substrate by at least a radial width of a notch at a periphery edge of said substrate, and

said substrate processing apparatus further comprises three or more support members which are disposed at the periphery edge of said atmosphere blocking member, abut on an edge surface of said substrate and accordingly support said substrate, and

a substrate supported on said support members and having a notch at a periphery edge of said substrate.

#### **Claims 10-46 (Canceled)**

#### **Claim 47 (Previously Presented)**

The substrate processing apparatus of claim 9, further comprising rotation means which rotates said substrate to which said processing liquid is supplied.

#### **Claim 48 (Previously Presented)**

The substrate processing apparatus of claim 47, wherein said rotation means rotates said atmosphere blocking member together with said substrate.

**Claim 49 (Canceled)**

**Claim 50 (Previously Presented)**

The substrate processing apparatus of claim 9, wherein each one of said support members comprises a contact surface which comes into a line contact with the edge surface of said substrate and supports said substrate.

**Claim 51 (Previously Presented)**

The substrate processing apparatus of claim 50, wherein a width of said contact surface is approximately the same as a width of a portion of said line contact.

**Claim 52 (Previously Presented)**

The substrate processing apparatus of claim 50, wherein a width of each one of said support members along a direction of said line contact becomes narrower with a distance away from said substrate or remains the same.

**Claim 53 (Previously Presented)**

A substrate processing system, comprising: a processing unit whose structure is the same as that of the substrate processing apparatus of claim 9; and  
a transportation unit which transports substrates to said processing unit.

**Claim 54 (Previously Presented)**

The substrate processing system of claim 53, further comprising a reversing unit which reverses substrates.

**Claim 55 (Currently Amended)**

A substrate processing apparatus wherein a processing liquid is supplied to one major surface of a substrate and one major surface is subjected to predetermined substrate processing, comprising:  
a processing liquid supply nozzle which supplies said processing liquid only to one major

surface of said substrate;

an atmosphere blocking member which has a shape of a disk and which is faced with other major surface of said substrate and that is away from said substrate; and

a gas supplying unit which supplies an atmosphere gas to a space which is created between said atmosphere blocking member and said substrate,

wherein a substrate-facing surface of said atmosphere blocking member which is faced with the other major surface of said substrate becomes closer to said substrate with a distance toward a periphery edge of said atmosphere blocking member over the entire circumference of said atmosphere blocking member, and

said atmosphere blocking member has a radius ~~diameter~~ which is smaller than a radius ~~diameter~~ of said substrate by at least a radial width of a notch at a periphery edge of said substrate, a substrate, said substrate having a notch at a periphery edge thereof.

#### **Claims 56-58 (Canceled)**

#### **Claim 59 (New)**

In combination, a substrate processing apparatus and a substrate, wherein a processing liquid is supplied to one major surface of a substrate for a predetermined substrate processing, comprising:

three or more support members disposed in said processing apparatus, which abut a peripheral edge of said substrate and accordingly support said substrate;

said substrate having a notch at said peripheral edge of said substrate;

an atmosphere blocking member which faces another major surface of said substrate and is spaced away from said substrate;

said atmosphere blocking member having a radius which is smaller than a radius of said substrate at least by a radial width of said notch at said peripheral edge of said substrate;

wherein a substrate-facing surface of said atmosphere blocking member which faces the other major surface of said substrate becomes closer to the other major surface of said substrate with a distance toward said peripheral edge of said atmosphere blocking member;

said three or more support members being disposed at a peripheral edge of said atmosphere

blocking member; and

a gas supplying unit which supplies an atmosphere gas to a space which is created between said atmosphere blocking member and said substrate.

**Claim 60 (New)**

The combination of claim 59, whereby the atmosphere blocking member prevents a mist from passing through said notch from said one major surface of said substrate, to said other major surface of said substrate.

**Claim 61 (New)**

The combination of claim 59, wherein said atmosphere blocking member and said notched substrate cooperate to prevent a mist generated by liquid processing of said one major surface of said substrate, from passing through said notch and reaching said other major surface of said substrate.